

## Abstract

The invention provides an indium oxide-tin oxide powder which can be produced at low cost and which can provide a high-density sputtering target having a prolonged target life, and a sputtering target employing the powder.

The indium oxide-tin oxide powder containing an In-Sn oxide as a predominant component is characterized in that the oxide powder contains no compound oxide ( $In_4Sn_3O_{12}$ ) detectable through X-ray diffraction and has a  $SnO_2$  solid solution amount in  $In_2O_3$  of 2.3 mass% or more, the  $SnO_2$  solid solution amount being calculated from the precipitated  $SnO_2$  content (mass%) obtained from the ratio between integral diffraction intensity attributed to  $In_2O_3$  (222) and integral diffraction intensity attributed to  $SnO_2$  (110).